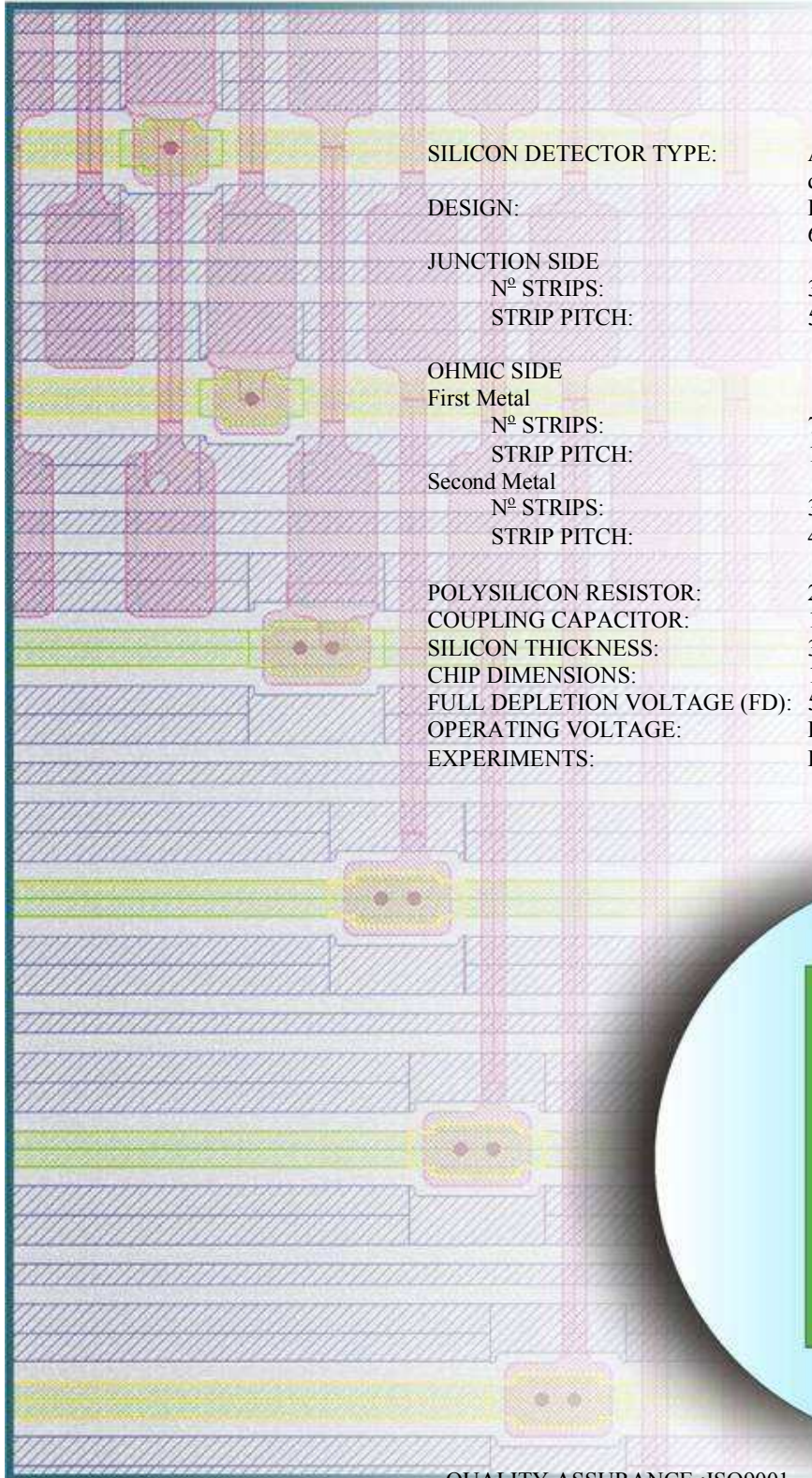
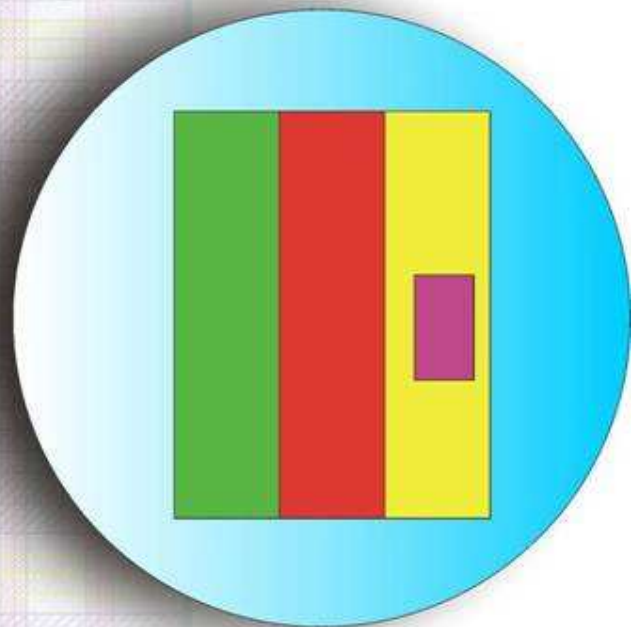


DESIGN DDD5

AC COUPLED ION IMPLANTED TOTALLY DEPLETED DOUBLE SIDED DOUBLE METAL MICROSTRIP DETECTOR



SILICON DETECTOR TYPE:	AC coupled ion implanted totally depleted silicon microstrip detector.
DESIGN:	Double sided, two metal layers on NN+ 6 inch wafer technology.
JUNCTION SIDE	
N° STRIPS:	384
STRIP PITCH:	50 μm
OHMIC SIDE	
First Metal	
N° STRIPS:	768
STRIP PITCH:	153.5 μm
Second Metal	
N° STRIPS:	384
STRIP PITCH:	49.5 μm
POLYSILICON RESISTOR:	2.5 \pm 0.5 M Ω
COUPLING CAPACITOR:	100 pF
SILICON THICKNESS:	300 \pm 10 μm
CHIP DIMENSIONS:	120.125 x 21.2 mm ²
FULL DEPLETION VOLTAGE (FD):	50 V maximum
OPERATING VOLTAGE:	FD to 2FD
EXPERIMENTS:	D2, FNAL



QUALITY ASSURANCE :ISO9001



MICRON SEMICONDUCTOR